L Number	Hits	Search Text	DB	Time stamp
1	0	11040681.URPN.	USPAT	2003/01/13 14:46
2	2	5726087.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:28
3	355	dry adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:49
4	518	(gate adj oxide) with angstrom with ("10" or "15" or "20")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:51
5	341	(gate adj oxide) with angstrom with ("10" or "15")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:23
6	234	((gate adj oxide) with angstrom with ("10" or "15")) and nitrid$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:06
7	46	((gate adj oxide) with angstrom with ("10" or "15")) same nitrid$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:06
8	8	(gate adj oxide) with angstrom with ("10" or "15") with (ultra near2 thin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:24
-	355	(gate with oxide) and (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:28
-	197	((gate with oxide) and (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	149	(((gate with oxide) and (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)) and 438/$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	119	((((gate with oxide) and (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)) and 438/$3.ccls.) and (gate with electrode)	USPAT; EPO; JPO; DERWENT	2002/07/30 13:55
-	145	(gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/31 15:55
-	76	((gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	59	(((gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)) and 438/$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	5	(gate with oxide) same (oxidiz$3 with substrate) and ((nitrid$5 with (no or (nitric with oxide)) same boron)) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/30 15:11
-	17	"5650344"	USPAT; EPO; JPO; DERWENT	2002/07/30 15:11
-	14	"5403786"	USPAT; EPO; JPO; DERWENT	2002/07/31 14:16

-	26	(gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd and ono and (gate adj electrode)	USPAT; EPO; JPO; DERWENT	2002/07/31 15:57
-	22	(gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with (silicon or polysilicon))	USPAT; EPO; JPO; DERWENT	2002/07/31 16:33
-	11	((gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with (silicon or polysilicon))) and tungsten	USPAT; EPO; JPO; DERWENT	2002/07/31 15:58
-	3	(gate with oxide) same (oxidiz$3 with substrate) and (nitrid$5 with (no or (nitric with oxide))) and cvd and ono and (((gate adj electrode) with polycide) same tungsten)	USPAT; EPO; JPO; DERWENT	2002/07/31 16:56
-	17	"5650344"	USPAT; EPO; JPO; DERWENT	2002/07/31 16:56
-	3554	(nitrid$5 with gate with oxide) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:32
-	0	((nitrid$5 with gate with oxide) same (nitirc adj oxide)) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:33
-	5	((nitrid$5 with gate with oxide) same (nitric adj oxide)) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:33
-	6	((nitrid$5 with gate with oxide) same (nitric adj oxide)) and cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 14:55